

Ph 11  
(294/1961)

UDC 538.632.08

# ACTA POLYTECHNICA SCANDINAVICA

**PHYSICS INCLUDING NUCLEONICS SERIES No. 11**

**TOR STUBB**

**The measurement of the Hall effect with the aid  
of microwaves in germanium specimens changing  
from n-type to p-type with changing temperature**

*Finnish Contribution No. 20*

**HELSINKI 1961**

# **ACTA POLYTECHNICA SCANDINAVICA**

*... a Scandinavian contribution to international engineering sciences*

Published under the auspices of the Scandinavian Council for Applied Research

in *Denmark* by the Danish Academy of Technical Sciences

in *Finland* by the Finnish Academy of Technical Sciences, the Swedish Academy of Engineering Sciences in Finland, and the State Institute for Technical Research

in *Norway* by the Norwegian Academy of Technical Science and the Royal Norwegian Council for Scientific and Industrial Research

in *Sweden* by the Royal Swedish Academy of Engineering Sciences, the Swedish Natural Science Research Council, and the Swedish Technical Research Council

*Acta Polytechnica Scandinavica consists of the following sub-series:*

*Chemistry including Metallurgy Series, Ch*

*Civil Engineering and Building Construction Series, Ci*

*Electrical Engineering Series, El*

*Mathematics and Computing Machinery Series, Ma*

*Mechanical Engineering Series, Me*

*Physics including Nucleonics Series, Ph*

For subscription to the complete series or to one or more of the sub-series and for purchase of single copies, please write to

## **ACTA POLYTECHNICA SCANDINAVICA PUBLISHING OFFICE**

Box 5073  
Stockholm 5

Phone 67 09 10

This issue is published by

**THE SWEDISH ACADEMY OF ENGINEERING SCIENCES IN FINLAND**

Helsingfors, Finland





**UDC 538.632.08**

**THE MEASUREMENT OF THE HALL EFFECT WITH THE AID  
OF MICROWAVES IN GERMANIUM SPECIMENS CHANGING  
FROM N-TYPE TO P- TYPE WITH CHANGING TEMPERATURE**

by

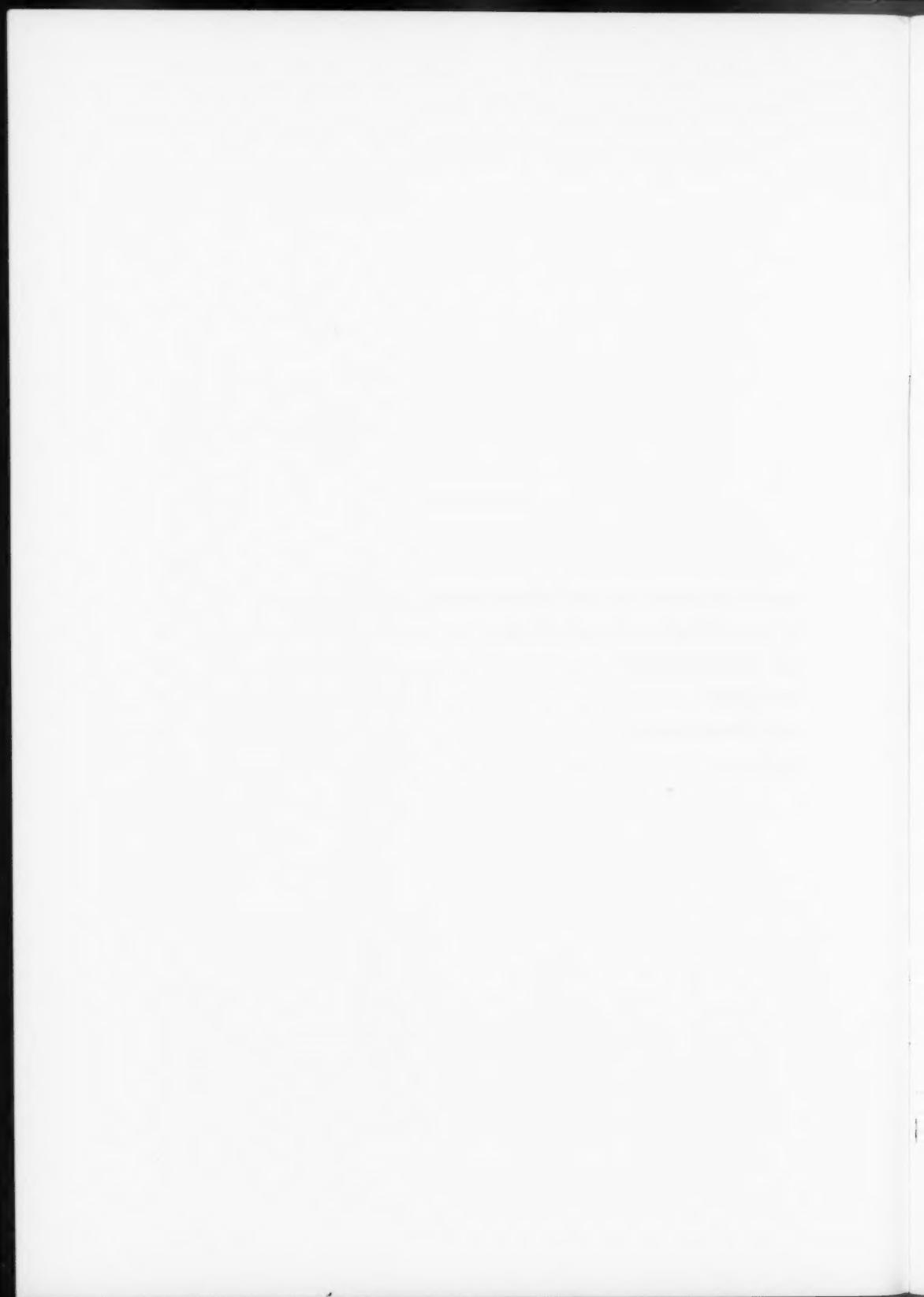
**TOR STUBB**

**ACTA POLYTECHNICA SCANDINAVICA**  
**Physics Including Nucleonics Series Ph 11**  
**(AP 294/1961)**

2

## CONTENTS

	Page
MEASURING PROCEDURE AND MEASUREMENTS.....	7
FITTING OF CONTACTS AND ETCHING .....	12
THE HALL CONSTANT .....	13
DISCUSSION .....	16
ACKNOWLEDGEMENT .....	18
REFERENCES.....	19



There are few experimental methods elucidating the properties of a semiconductor material as fully as measurements of the Hall effect. Such measurements are usually carried out with direct current, but recently various high-frequency measuring methods have been treated theoretically as well as experimentally [1-12]. Hambleton & Gärtner [10] have shown that no difference can be demonstrated between D.C. measurements and microwave measurement up to 24 GHz, whereas an essential departure from the D.C. measurements can be discovered on 70 GHz, [12].

In all high-frequency transport phenomena, the free carriers are out of phase with the superimposed high-frequency field, owing to the inertia of the carriers. No exact solution of this problem has been given, but one may approximately write for the Hall mobility:

$$\mu_H = \frac{q}{m(\omega_e + j\omega)} \quad (1)$$

where

- $q$  the electron charge
- $m$  the effective mass of the carriers
- $\omega_e$  the collision frequency of the carriers
- $\omega$  the angular frequency of the high-frequency electromagnetic

The present work is a study of the Hall effect with the aid of microwaves in the X-band. Measurements were carried out by two different methods. The first method is based on the principle worked out by Nishina & Spry [9]. It is well applicable to measurements at constant temperature and with varying magnetic field but the resonator has to be tuned after any change of temperature. Large errors are thereby incurred, which are difficult to account for later. The measuring

accuracy with this method also decreases rather strongly, as there is a leakage effect dependent on the magnetic field even when the resonator is empty. The final measuring equipment was a modification of Hambleton and Grtner's [ 10 ] equipment.

#### MEASURING PROCEDURE AND MEASUREMENTS

The system used for the measurements contains a crystal holder as shown in Fig. 1a. It consists of two waveguide sections whose axes are perpendicular and whose common wall has been replaced by the semiconductor crystal. The thickness of the crystal was 1 mm in our measurements. The electric field in the input waveguide produces a current in the sample in the vertical direction. The D.C. magnetic field applied perpendicular to the face of the crystal generates a microwave Hall voltage in a horizontal direction, which couples to the output waveguide. A simple analysis indicates that Hall mobility is related to the microwave powers in the applied and observed fields at the faces of the crystal in the following manner [12]:

$$\mu_H = \frac{I}{H} \left[ \frac{P_{out}}{P_{in}} \right]^{1/2} \quad (2)$$

where

$H$  the magnitude of the applied magnetic field

$P_{in}$  the power in the electric field at the input face of the crystal

$P_{out}$  the power in the electric field at the output face of the crystal.

Equation (2) is only valid for strong magnetic fields.

In order to achieve the best possible tuning of the system, the cryostat has been designed so that the tuning screws are located outside the cryostat itself. With such a design, the waveguide has to consist of German silver, as well as the cryostat proper. The latter has been made with double walls and the outer space has been evacuated. The entire microwave system was insulated from the magnet by means of a polystyrene sheet.

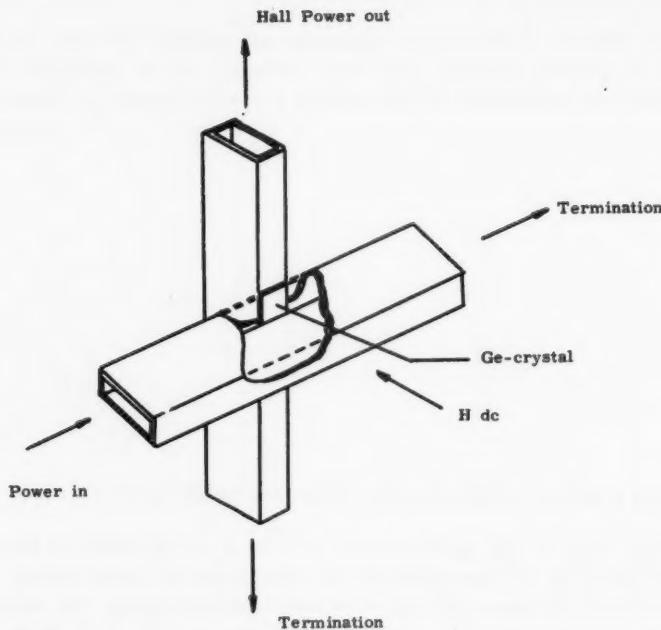


Fig 1 a.

The sample under measurement could be cooled down to 100°K in this device with the aid of liquefied air and by continuous evacuation of the system. It is particularly essential that the sample is in high vacuum or in a rare gas atmosphere so that the surface potential of the crystal is positively definable and its surfaces are not affected by moisture. The temperatures were measured with the aid of an STE 100 nickel resistance.

The entire microwave bridge is inserted in a microwave circuit similarly as was done by Hambleton & Gärtnert [10], except that an extra attenuation shown in Fig. 1b was used. Moreover, the standing wave ratio was measured in both branches for different magnetic fields. An HP 820A signal generator was used. The frequency meter was of resonator type, manufactured by Sivers under the type designation SL 5205, while the standing wave indicator was type SL 5141/1. The amplifier was Kintel 203, with a Varian recorder as ultimate indicator. The attenuator was of the HP 885A type.

On very high frequencies variations can be shown to occur in the measurements, obviously resulting from tuning difficulties [12]. Similar differences were found in the present measurements, but they were entirely attributable to the positioning of the crystal. The crystal has to be placed symmetrically with respect to both waveguides, and it has to be framed with silver emulsion so that no leakage occurs along the edges.

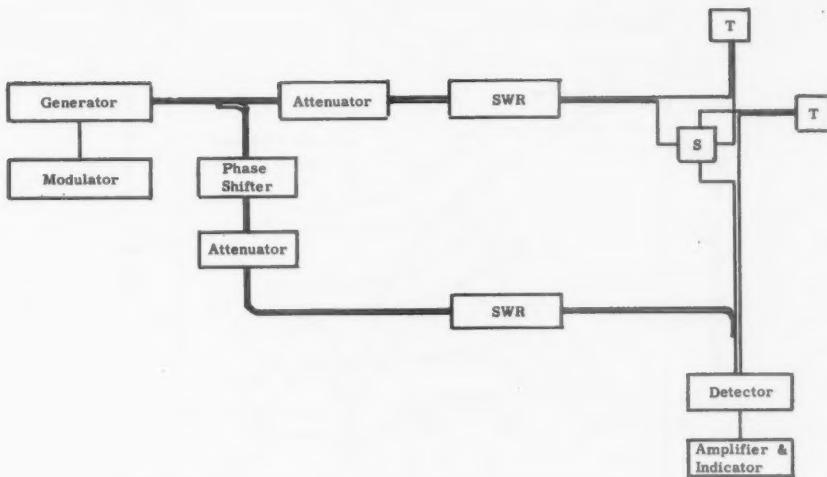


Fig. 1 b.

The equipment in its entirety was constructed for the purpose of Hall effect measurements having bearing on a complex of problems concerning the semiconductor properties of boron. As a check of the apparatus, measurements were made with germanium, which revealed an absorption in the Hall constant at  $240 - 250^{\circ}$  K.

As the crystals were primarily intended to be used for a check of the apparatus, their impurities were not known beforehand. However, it could be shown by quantitative spectral investigation that Al as well as Cu occur in the samples. Furthermore, the orientation of the crystals, the occurrence of dislocations and the etch-pitch distribution were investigated because absorption may occur on account of dislocations.

Measurement of the resistivity as a function of temperature by D.C. revealed a jump at the point where absorption occurred, Figs. 2, b and 3, b.

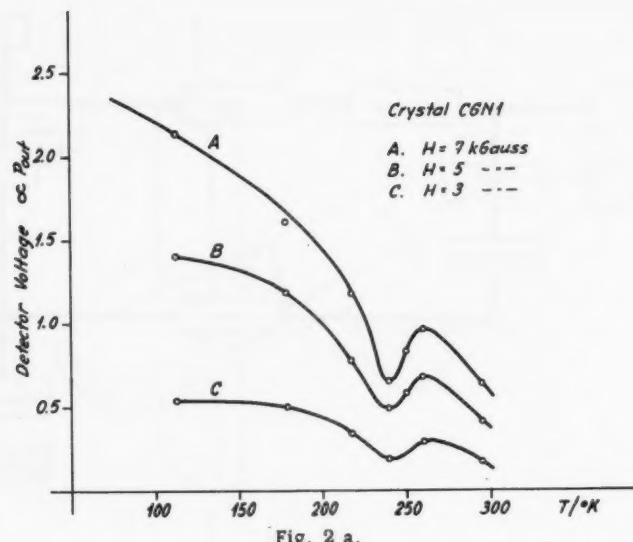


Fig. 2 a.

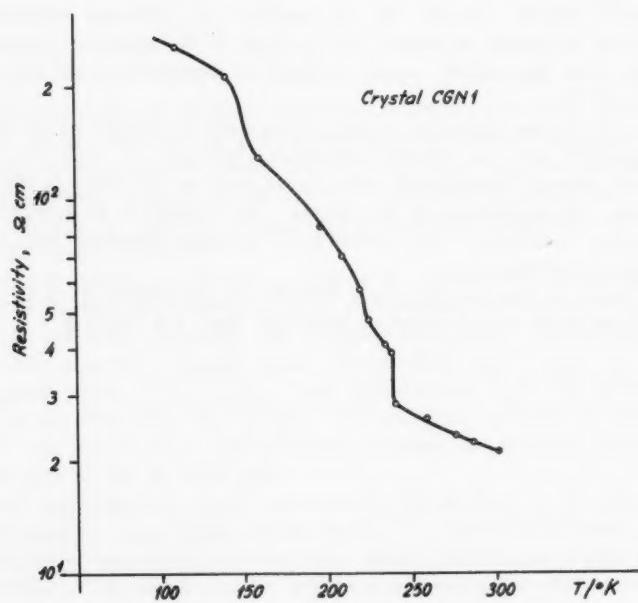


Fig. 2 b.

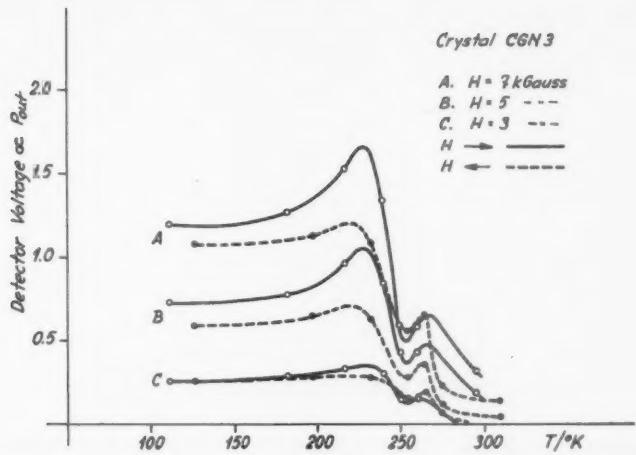


Fig. 3 a.

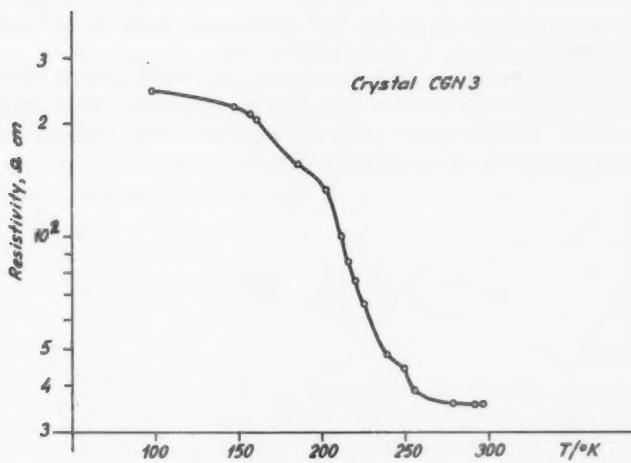


Fig. 3 b.

#### FITTING OF CONTACTS AND ETCHING

In order to obtain a barrier-less layer in the D.C. measurements, various methods were tried. According to Schotky [13], an evaporated metal coating on a semiconductor provides barrier free contact. This is true if the electron release energy of the metal exceeds that of the semiconductor. Contacts of this kind have been thoroughly investigated by Irmler [14]. In the present instance the following, method was used: The germanium surface was galvanically coated with Cu. The Cu atoms were then diffused into the germanium sample at 350°C and the surface was ground with emery paper. An Au layer was evaporated onto this surface. This procedure produces a barrier-free layer for temperatures down to 100°K, which is the lowest temperature employed in the present work.

A WAg solution was used for etching the samples, with +35°C initial temperature of the bath. It is important to make sure that no Ag atoms remain on the surface after etching, as they might form a conductive layer and prevent the high-frequency power from penetrating the crystal.

### THE HALL CONSTANT

In a region, in which the type of impurity mainly consists of electrons or holes, one may write for the Hall constant  $R_H$ :

$$R_H = - \frac{\mu_H}{\mu} \frac{I}{q n} \quad (3)$$

where the negative sign refers to electrons and the positive sign to holes. The ratio of Hall mobility and drift mobility  $\mu_H/\mu$ , is dependent on the various scattering mechanisms and the shape of the energy surfaces.  $n$  stands for the number of carriers in the semiconductor.

The scattering processes in the crystals in question are unknown and no study can therefore be made of the ratio  $\mu_H/\mu$ . Its value approaches unity for high magnetic field strengths and for degenerative semiconductors. If a model having spherical energy surfaces and Boltzmann's statistics are employed and if the assumption is made that the relaxation time is independent of energy,  $\mu_H/\mu$  can be assumed to have the value  $3\pi/8$ , as is well known.

In the case of samples in which electrons as well as holes contribute to the conductivity, one may write for  $R_H$ :

$$R_H = - \frac{3\pi}{8q} \frac{n\mu_n - p\mu_p^2}{(n\mu_n + p\mu_p)^2} \quad (4)$$

where

- $n$  the number of electrons per unit volume
- $p$  the number of holes per unit volume
- $\mu_n$  the electron mobility
- $\mu_p$  the hole mobility
- $q$  the electron charge.

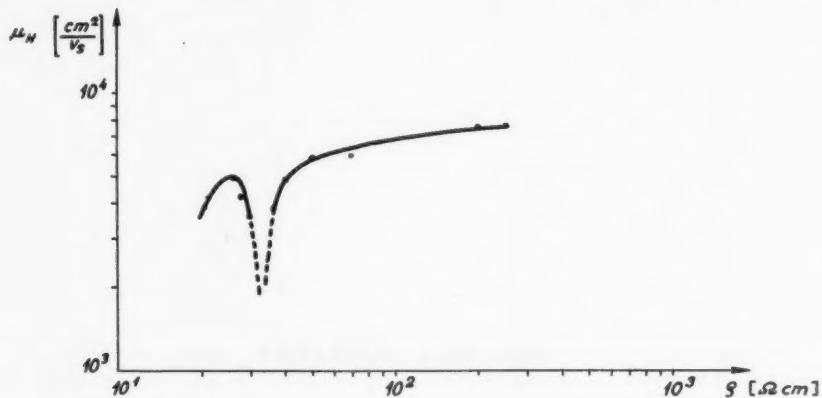


Fig. 4.

The formula (4) is only approximate and applies under the conditions stated for  $\mu_H / \mu$ , and for weak magnetic fields. A detailed study of  $R_H$  as a function of  $H$  has been made by Harman [15] and by Howord [16].

It can be seen from the measured curve, Fig. 4, that temperature dependence of the Hall constant is insignificant at low temperatures. This is due to the fact that the impurities are still ionized and the ionization energy is low for donors as well as acceptors.

If  $\mu_n / \mu_p < 1$ ,  $R_H$  is negative for all samples of n-type in the entire temperature interval. For samples of p-type,  $R_H$  will change its sign when  $n\mu_n^2 = p\mu_p^2$ . The Hall constant has a maximum at a temperature slightly higher than that at which  $R_H$  changes its sign.

The n value for maximum  $R_H$  is [17]:

$$n = (N_A - N_D) / \left( \frac{\mu_H}{\mu} - 1 \right) \quad (5)$$

where

$N_A$  the number of acceptor levels  
 $N_D$  the number of donor levels.

The value of  $R_{H_{\max}}$  can therefore be calculated by the formula

$$R_{H_{\max}} = \left[ \frac{-3\pi}{8q(N_A N_D)} \right]^2 \frac{(b-1)^2}{4b} \quad (6)$$

where  $b$  denotes the ratio  $\mu_n / \mu_p$ . In the exhaustive range, there is

$$R_{H_{ex}} = \frac{3\pi}{8q(N_A - N_D)} \quad (7)$$

Substitution of (6) and (7) yield the value of  $b$ , i.e.,

$$\frac{b^2 - 1}{4b} = -\frac{R_{H_{max}}}{R_{H_{ex}}} \quad (8)$$

## DISCUSSION

In order to gain some kind of control of impurities occurring in the sample,  $R_H$  was plotted as a function of  $1/T$ ; Fig. 5.

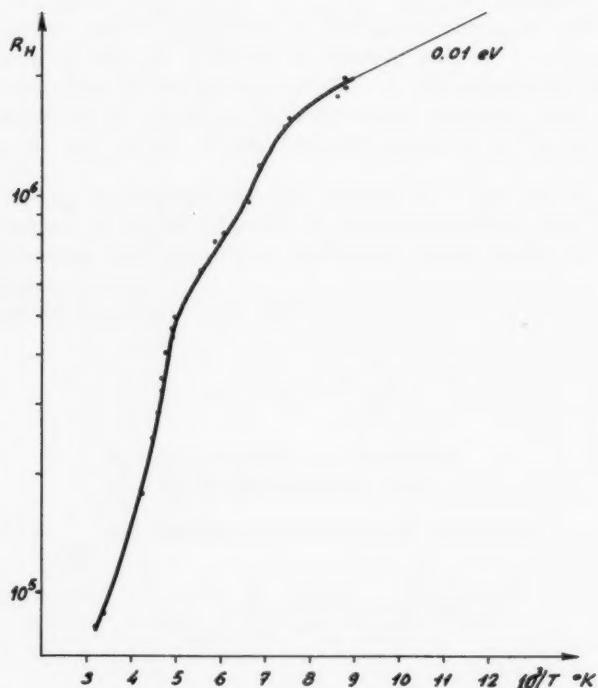


Fig. 5.

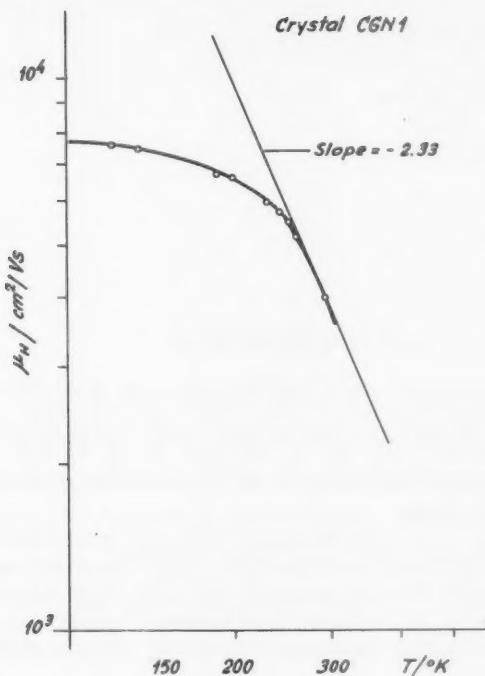


Fig. 6.

It can be seen that the ionization energy becomes 0.01 eV at low temperatures, which is the ionization energy for aluminium acceptors. Furthermore, Fig. 6, showing  $\mu_H$  as a function of  $T$ , reveals that the mobility is proportional to  $T^{-2.33}$ , as has been previously demonstrated, e.g., by Morin & Maita[17].

The rapid change in resistivity at 240°K is hard to explain since the impurities in the crystal are unknown. Under any circumstances, transition from one impurity level to another must be concerned. It is likely that transition occurs from the aluminium level to a copper level.

The measuring method employed in this work is particularly reliable and has the great advantage over D.C. measurements that no contacts are required on the crystal. This advantage can be fully exploited at low temperatures and with high-ohm silica crystals.

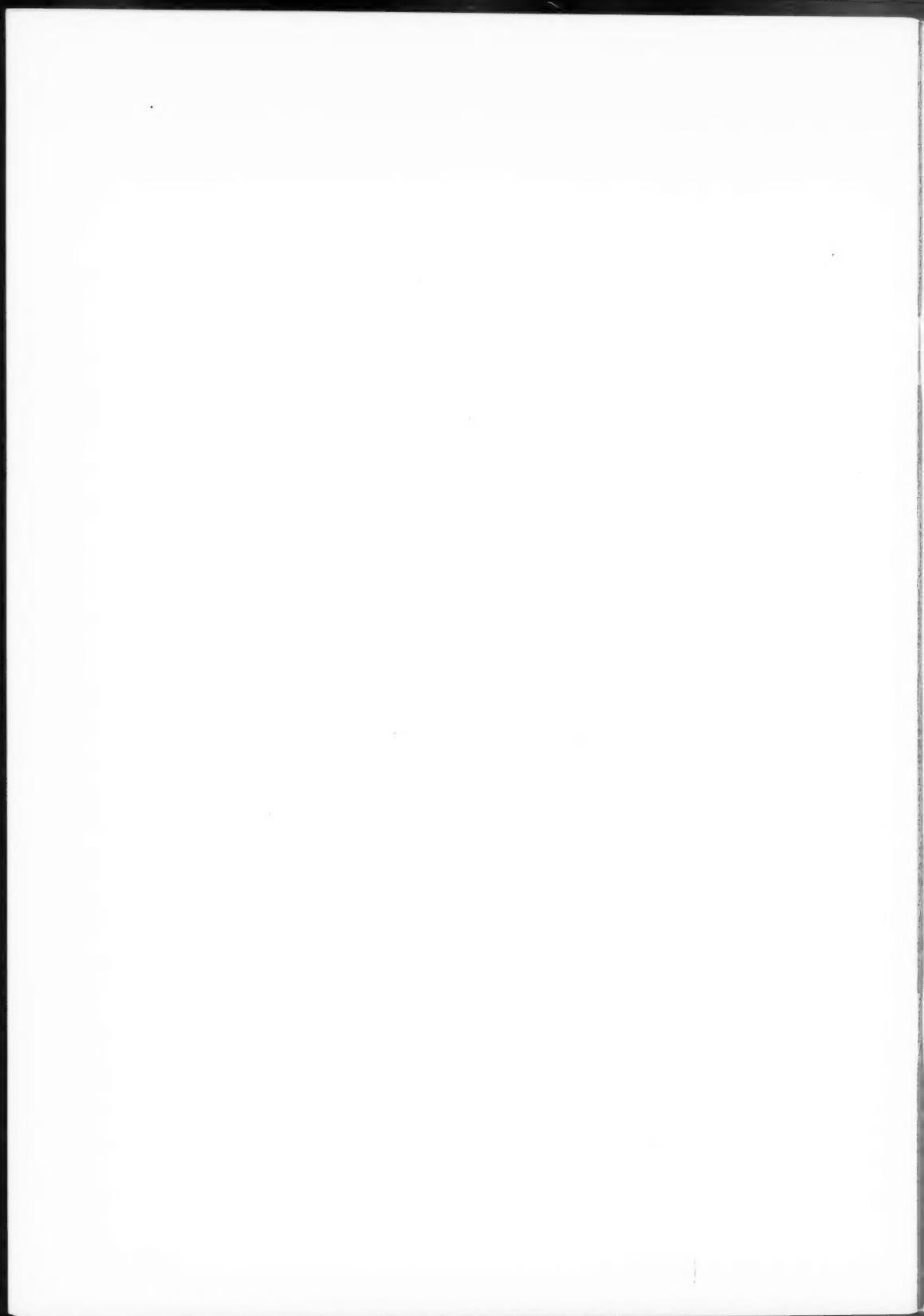
#### ACKNOWLEDGEMENT

The author is indebted to Dr. M. Cardona and Prof. B. Agdur for discussions concerning this problem and to Prof. E. Laurila for advice and directions received at various stages of my work. Mr. J. Tallqvist, M.Sc. in Eng., and Mr. O. Wiio, M.Sc. in Eng., have assisted me in the microwave measurements, for which my thanks are due to them.

This work is part of a group of studies concerning semiconductor problems, which have received economic assistance from Valtion Luonnonmieteellinen Toimikunta (Finnish scientific Research Council), Tekniikan Edistämissäätiö (The Foundation for Promotion of Technique) and Svenska Tekniska Vetenskapsakademien i Finland (The Swedish Academy of Engineering Sciences in Finland).

## REFERENCES

1. S. Cooke, Phys. Rev. 74. ( 1948 ) p. 701.
2. H. Barlow. Proc. I.R.E. 102B. ( 1954 ) p. 179.
3. B. Donovan, Proc. Phys. Soc. ( London ) A67. ( 1955 ) p. 305.
4. B. Donovan, Proc. Phys. Soc. ( London ) A68. ( 1955 ) p. 1026.
5. R. Rau and M. Casperi, Phys. Rev. 100. ( 1956 ) p. 632.
6. H. Barlow. and L. Stephenson, Proc. I.E.E. 103B. ( 1956 ) p. 110.
7. B. Donovan and N. March, Proc. Phys. Soc. ( London ) B69. ( 1956 ) p. 528.
8. T. Fukuroyi and M. Date, Sci. Repts. Research Inst. Tohoku University, Ser. A, Vol. 9. ( 1957 ) p. 190.
9. Y. Nishina and W. Spry, J. Appl. Phys. 29. ( 1958 ) p. 230.
10. G. Hambleton and W. Gärtner, Bull. APS II. 3. ( 1959 ) p. 259.
11. G. Hambleton and W. Gärtner, J. Chem. Phys. Solids. 8. ( 1959 ) p. 329.
12. G. Hambleton and W. Gärtner, Microwave Res. Inst., Symp. Ser IX ( 1959 ) p. 87.
13. W. Schottky, Z. Phys. 113. ( 1939 ) p. 367.  
Z. Phys. 118. ( 1942 ) p. 539.
14. H. Irmiger, Über Entstehung und Wirkung von Störstellen mit tiefen Energieniveaus in Silicium. Berlin 1959. Thesis.
15. T. Harman, T. Willardson and A. Beer, Phys. Rev. 95. ( 1954 ) p. 699.
16. D. Howarth, Proc. Roy. Soc 70B. ( 1957 ) p. 124.
17. F. Morin and J. Maita, Phys. Rev. 96. ( 1954 ) p. 28.



**THE LAST VOLUMES OF  
ACTA POLYTECHNICA PHYSICS INCLUDING NUCLEONICS SERIES**  
(The predecessor of Acta Polytechnica Scandinavica)

**Volume 3**

- Nr 1 SVARTHOLM, N: *Two Problems in the Theory of the Slowing Down of Neutrons by Collisions with Atomic Nuclei.* ACTA P 177 (1955), 15 pp, Sw. Kr. 5: 00 UDC 539.185.7
- Nr 2 BOLINDER, F E: *The Relationship of Physical Applications of Fourier Transforms in Various Fields of Wave Theory and Circuitry.* ACTA P 189 (1956), 22 pp, Sw. Kr 6: 00 UDC 517.512.2:621.37
- Nr 3 BRUNDELL, P-O, and ENANDER, B: *The Neutron-Proton System with a Central Exponential Potential. II.* ACTA P 190 (1956), 13 pp, Sw. Kr 2: 00 UDC 530.245:539.185
- Nr 4 BÄCKSTRÖM, M: *Einfache Theorie der Gassirkulation in Sorptionskälteapparaten nach v. Platen und Munters.* ACTA P 195 (1956), 71 pp, Sw. Kr 8: 00 UDC 681.575
- Nr 5 GRANSTRÖM, S A: *Loading Characteristics of Air Blasts from Detonating Charges.* ACTA P 196 (1956), 93 pp, Sw. Kr 10: 00 UDC 624.042.3:533.6.012.72
- Nr 6 STRANDELL, N: *A Photographic Method of Studying the Spread of Trochoidal Electron Beams.* ACTA P 204 (1956), 13 pp, Sw. Kr 2: 50 UDC 681.385.16.337.533.7.087.5
- Nr 7 ZIMEN, K E: *Diffusion von Edelgasatomen die durch Kernreaktion in festen Stoffen gebildet werden (Edelgasdiffusion in Festkörpern 1)*  
INTHOFF, W, und ZIMEN, K E: *Kinetik der Diffusion radioaktiver Edelgase aus festen Stoffen nach Bestrahlung (Edelgasdiffusion in Festkörpern 2)* ACTA P 206 (1956), 7+15 pp, Sw. Kr 6: 00 UDC 533.25:546.29-16:539.17
- Nr 8 BÄCKSTRÖM, M: *Entropy-Enthalpy Diagram for Water Vapour and Liquid Extended to Higher Temperatures and Pressures.* ACTA P 207 (1956), 23 pp, Sw. Kr 5: 00 UDC 536.722:536.75:621.1.02(084.82)
- Nr 9 MEYER, N I: *Switching Time in P-N Junction Diodes with Built-In Drift Field.* ACTA P 210 (1957), 32 pp, Sw. Kr 5: 00 UDC 537.322.33
- Nr 10 OLSEN, H, ROMBERG, Wand WERGELAND, H: *Reaction of Sound Waves and its Application for Absolute Measurement of Intensity.* ACTA P 226 (1957), 13 pp, Sw. Kr 7: 00 UDC 534.61
- Nr 11 ANDERSSON, B J: *Studies on the Circulation in Organic Systems with Applications to Indicator Methods.* ACTA P 229 (1957), 19 pp, Sw. Kr 3: 00 UDC 618.13:533.574.8

**ACTA POLYTECHNICA SCANDINAVICA  
PHYSICS INCLUDING NUCLEONICS**

- Ph 1 FANT, C G M: *Modern Instruments and Methods for Acoustic Studies of Speech.* (Acta P. 246/1958), 83 pp, Sw. Kr 7: 00 UDC 534.134:618.789.
- Ph 2 STUBB, T: *The Measurement of Conductivity in Semiconductors with the aid of Microwaves.* (Acta P. 259/1959) 14 pp, Sw. Kr. 7.00 UDC 537.311.33
- Ph 3 STUBB, T: *Untersuchung über die Lebensdauer der Minoritätsträger in Germanium.* (Acta P. 269/1960) 17 pp, Sw. Kr. 7.00 UDC 537.311.33
- Ph 4 ROOS, MATTS: *Approximate gamma ray flux calculations outside a reactor core.* (Acta P. 273/1960) 24 pp, Sw. Kr. 7.00 UDC 539.122:621.039.538
- Ph 5 HÄRLIN, A: *Elementary Analysis and Heat Values and WIDELL, T: Enthalpy Diagram for Fluorine Gases.* (Acta P. 275/1960) 28 pp, Sw. Kr. 7: 00 UDC 536.662 + 536.722
- Ph 6 CYVIN, SVEN J: *Mean Amplitudes of Vibration in Molecular Structure Studies.* (Acta P. 279/1960) 226+6 pp, Sw. Kr. 7: 00 UDC 539.19
- Ph 7 JENSEN, ERLING: *General Theory on Spin Echoes for Any Combination of any Number of Pulses. Introduction of a simple «Spin-Echo Diagram».* (Acta P. 283/1960) 20 pp, Sw. Kr. 7: 00 UDC 539.143.4
- Ph 8 MORCH, K. A.: *Measurement of Total Acoustic Power of Sources of Sound in a Reverberation Chamber.* (Acta P. 286/1960). 25 pp, Sw. Kr. 7:00. UDC 534.62
- Ph 9 JÄÄSKELÄINEN, P.: *On Microwave Conductivity, Noise, and Oscillations of Gas Discharge Plasma.* (Acta P. 291/1960). 24 pp, Sw. Kr. 7:00. UDC 537.562:621.391.822.2
- Ph 10 FORWALD, HAAKON: *Wave Phenomena in Compressed-Air Ducts.* (Acta P. 292/1961). 147 pp, Sw. Kr. 14:00. UDC 533.17:534.213.4-13:621.315.54

**Price Sw. Kr. 7.00**

